

MAY 07 2004

OFFICIAL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Tony P. Chiang, Karl F. Leaser
Assignee: Angstrom Systems, Inc.
Title: Method and Apparatus for Improved Temperature Control In Atomic Layer Deposition
Serial No.: 09/854,092 Filing Date: May 10, 2001
Examiner: Timothy Howard Meeks Group Art Unit: 1762
Docket No.: PA1663US
(ANS-PA1663US)

San Jose, California
May 7, 2004

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Dear Sir:

In response to the March 9, 2004 restriction requirement, Applicants hereby elect the claims in Group I (Claims 1-15 and 44-47) drawn to a depositing method, classified in class 427, subclass 255.7, for further prosecution in the above patent application. Applicants reserve the right to prosecute the remaining claims in a divisional application.

Should the Examiner have any questions, the Examiner is invited to call the undersigned at (408) 382-0480.

Certification of Facsimile Transmission

I hereby certify that this paper is being facsimile transmitted to the U.S. Patent and Trademark Office on the date shown below.

Signature

Date

Respectfully submitted,

Brian D. Ogonowsky
Attorney for Applicant(s)
Reg. No. 31,988